

**REMARKS**

Applicants appreciate the indication of allowable subject matter in claims 1-3 and 11. Claims 4-10 remain rejected under 35 U.S.C. §102(b) for anticipation by, or in the alternative under 35 U.S.C. §103(a) for obviousness over, WO 97/35939 as interpreted by U.S. Patent No. 6,261,357 to Egami et al. This rejection is traversed in view of the amendments to claims 4-10 and for the following reasons.

The substrate coated with a silica-containing film of the present invention is produced by a process which results in a low-density film with a low-dielectric constant having essentially no pores or voids of more than 10 nm in diameter. That feature is now required in all of claims 1-10. Claim 3 is amended to depend from claim 1. Claims 4-10 are amended to clarify that the claimed substrate includes the features of claim 1. No new matter has been added.


As recognized in the Final Office Action, Egami fails to teach or suggest the claimed pore diameters of claims 1-10.

In view of the amendments to claims 3-10, all of claims 1-10 are believed to define over the prior art and be in condition for allowance.

Finally, the Examiner failed to initial the Form PTO/SB/08A (submitted on December 4, 2003) next to the two Japanese documents. Those documents, as well as English language abstracts thereof, were submitted in the parent application (09/530,437) and are also discussed on page 2 of the application. Acknowledgment of consideration thereof, as well as for the references in Form PTO/SB/08A submitted November 18, 2004, is requested.

Respectfully submitted,

WEBB ZIESENHEIM LOGSDON  
ORKIN & HANSON, P.C.

By 

Kent E. Baldauf  
Registration No. 25,826  
Attorney for Applicants  
700 Koppers Building  
436 Seventh Avenue  
Pittsburgh, Pennsylvania 15219-1818  
Telephone: 412-471-8815